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PATENT

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant:	Hou, Chien-Chou; et al.)	Examiner:	Deo, Duy Vu N'Guyen
Serial No.:	10/600,377)	Art Unit:	1765
Filed:	June 20, 2003)	Our Ref:	B-5130 621033-6
For:	"METHOD OF ETCHING UNIFORM SILICON LAYER")	Date:	June 8, 2005
)	Re:	<i>Amendment and Response</i>

AMENDMENT AND RESPONSE

Mail Stop Amendment
Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Sir:

This is in reply to the non-final Office Action mailed on March 9, 2005, an initial response to which is due no later than

June 9, 2005.

Please amend the above-identified application as described below and consider the following remarks. **All amendments and remarks herein are made without prejudice.**

Amendments to the Claims are reflected in the listing of claims that begins on page 2 of this paper.

Remarks/Arguments begin on page 5 of this paper.